Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1089	((oxygen with plasma) same aluminum) and (@py<"2000")	USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 16:23
L2	872	((oxygen with plasma) same ((aluminum oxide) or alumina or (aluminum with (film or layer or substrate)))) and (@py<"2000")	USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 16:24
L3	.5	L2 and ((trimethyl aluminum) or (tri-methyl aluminum))	USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 16:25
S1	2557	(427/248.1).CCLS.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	OFF	2006/10/26 09:21
S3	14	sherman-arthur.in.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON .	2006/10/26 09:16
S4	1545	(427/569).CCLS.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	OFF	2006/10/26 09:16
S5	0	S1 and ((trimethyl aluminum) or (tri-methyl aluminum) or (tri methyl aluminum) or (tri methyl aluminum) or (tma) or ("alch.sub. 3")) and ((aluminum oxide) or alumina or ("al.sub.2o.sub.3")) and (oxygen with (radical plasma atomic))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 11:29
S6	0	S4 and ((trimethyl aluminum) or (tri-methyl aluminum) or (tri methyl aluminum) or (tri methyl aluminum) or (tma) or ("alch.sub. 3")) and ((aluminum oxide) or alumina or ("al.sub.2o.sub.3")) and (oxygen with (radical plasma atomic))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 09:24
S7	10	S4 and ((trimethyl aluminum) or (tri-methyl aluminum) or (tri methyl aluminum) or (trialch.sub. 3")) and ((aluminum oxide) or alumina or ("al.sub.2o.sub.3"))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 09:24
S8	39	S1 and ((trimethyl aluminum) or (tri-methyl aluminum) or (tri-methyl aluminum) or ("alch.sub. 3")) and ((aluminum oxide) or alumina or ("al.sub.2o.sub.3"))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 09:27

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S9	1067	((atomic layer deposition) or (ald) or (atomic layer epitaxy) or ale or (sequential chemical vapor deposition) or \$3cvd) and ((trimethyl aluminum) or (tri-methyl aluminum) or (tri methyl aluminum) or (tma) or ("alch.sub.3")) and ((aluminum oxide) or alumina or ("al.sub.2o.sub.3"))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 10:42
S10	298	((atomic layer deposition) or (ald) or (atomic layer epitaxy) or ale or (sequential chemical vapor deposition) or \$3cvd) and ((trimethyl aluminum) or (tri-methyl aluminum) or (tri methyl aluminum) or (tma) or ("alch.sub.3")) and ((aluminum oxide) or alumina or ("al.sub.2o.sub.3")) and (oxygen with (atomic or plasma or radical))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON The state of th	2006/10/26 09:29
S11	102	S9 and (@py<"2000")	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 09:45
S12	475	((atomic layer deposition) or (ald) or (atomic layer epitaxy) or ale or (sequential chemical vapor deposition) or (sequential cvd)) and ((trimethyl aluminum) or (tri-methyl aluminum) or (tria) or ("alch.sub.3")) and ((aluminum oxide) or alumina or ("al.sub.2o.sub.3"))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ.	ON	2006/10/26 10:45
S13	3	((atomic layer deposition) or (ald) or (atomic layer epitaxy) or ale or (sequential chemical vapor deposition) or (sequential cvd)) and ((trimethyl aluminum) or (tri-methyl aluminum) or (trial) or ("alch.sub.3")) and ((aluminum oxide) or alumina or ("al.sub.2o.sub.3"))	USOCR; EPO; JPO	ADJ	ON	2006/10/26 11:00
S14	187	("4058430" "4389973" "4767494" "4845049" "4859627" "4876218" "4993357" "5060595" "5071670" "5130269" "5166092" "5225366" "5256244" "5270247" "5693139").PN. OR ("5916365"). URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/10/26 10:49

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S15	15	("4058430" "4389973" "4767494" "4845049" "4859627" "4876218" "4993357" "5060595" "5071670" "5130269" "5166092" "5225366" "5256244" "5270247"	US-PGPUB; USPAT; USOCR	OR	ON	2006/10/26 10:49
S16	1276	((atomic layer deposition) or (ald) or (atomic layer epitaxy) or ale or (sequential chemical vapor deposition) or (sequential cvd)) and ((aluminum oxide) or alumina or ("al.sub.2o.sub.3"))	USOCR; EPO; JPO	ADJ	ON	2006/10/26 11:18
S17	15	((atomic layer deposition) or (ald) or (atomic layer epitaxy) or ale or (sequential chemical vapor deposition) or (sequential cvd)) and ((aluminum oxide) or alumina or ("al.sub.2o.sub.3"))	EPO; JPO	ADJ	ON	2006/10/26 11:00
S18	0	((atomic layer epitaxy) or (sequential chemical vapor deposition) or (sequential cvd)) and ((aluminum oxide) or alumina or ("al.sub.2o.sub.3"))	USOCR	ADJ	ON	2006/10/26 11:04
S19	500	((atomic layer deposition) or (ald) or (atomic layer epitaxy) or ale or (sequential chemical vapor deposition) or (sequential cvd)) and (oxygen with (atomic or plamsa or radical))	USOCR; EPO; JPO	ADJ	ON	2006/10/26 11:19
S20	8	((atomic layer deposition) or (ald) or (atomic layer epitaxy) or ale or (sequential chemical vapor deposition) or (sequential cvd)) and (oxygen with (atomic or plamsa or radical))	EPO; JPO	ADJ	ON	2006/10/26 11:19
S21	473	((atomic layer deposition) or (ald) or (atomic layer epitaxy) or ale or (sequential chemical vapor deposition) or (sequential cvd)) and (oxygen with (atomic or plamsa or radical))	USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 11:22
S22	17	(remote same (oxygen with (atomic or plamsa or radical))) and ((trimethyl aluminum) or (tri-methyl aluminum) or (trial) or (trial) or ("alch.sub.3")) and ((aluminum oxide) or alumina or ("al.sub.2o.sub.3"))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 11:31

S23	399	(oxygen with (atomic or plamsa or radical)) and ((trimethyl aluminum) or (trimethyl aluminum) or (trimethyl aluminum) or (trimethyl aluminum) or (tma) or ("alch.sub.3")) and ((aluminum oxide) or alumina or ("al.sub.2o. sub.3"))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 11:31
S24	170	(oxygen with (atomic or plamsa or radical)) and ((trimethyl aluminum) or (trimethyl aluminum) or (trimethyl aluminum) or (tma) or ("alch.sub.3")) and ((aluminum oxide) or alumina or ("al.sub.2o. sub.3"))	USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 11:34
S25	75	remote with oxygen with plasma and (@py<"2000")	USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/10/26 16:20